

Title (en)
ION BEAM ARRANGEMENT

Publication
EP 0233083 A3 19880622 (EN)

Application
EP 87301202 A 19870212

Priority
GB 8603585 A 19860213

Abstract (en)
[origin: EP0233083A2] An ion beam arrangement accepts a steady beam of ions from an ion source and forms a stream of ion bunches from it, so that the bunches or packets of ions can be subsequently utilised. The ion beam buncher consists of an electrode (2) to which a high frequency alternating potential (14) is applied to impart a velocity modulation to ions within the steady beam. This electrode is followed by a drift space (3) in which the velocity modulation results in the formation of the discrete bunches of ions, but without any overall increase in ion energy. These ion bunches can then be accelerated to high energy levels using a multistage alternating voltage linear accelerator (24, 25).

IPC 1-7
H05H 9/00

IPC 8 full level
H01J 37/08 (2006.01); **H01J 37/317** (2006.01); **H05H 9/00** (2006.01)

CPC (source: EP)
H05H 9/00 (2013.01)

Citation (search report)

- [X] US 2860279 A 19581111 - HESTER ROSS E, et al
- [X] US 2813996 A 19571119 - MARVIN CHODOROW
- [A] FR 1231910 A 19601004 - VARIAN ASSOCIATES
- [A] GB 1046531 A 19661026 - HITACHI LTD

Cited by
EP2161724A4; US8106366B2

Designated contracting state (EPC)
AT BE CH DE ES FR GB GR IT LI LU NL SE

DOCDB simple family (publication)
EP 0233083 A2 19870819; EP 0233083 A3 19880622; GB 2186736 A 19870819; GB 8603585 D0 19860319; JP S62295400 A 19871222

DOCDB simple family (application)
EP 87301202 A 19870212; GB 8603585 A 19860213; JP 3132587 A 19870213